



D. Thin Film Process Technology 분과

2021년 1월 27일(수), 09:00-10:30 / 채널 A

[WA1-D] Metallic Films

좌장: 김우희 교수 (한양대학교), 한정환 교수 (서울과학기술대학교)

<p>WA1-D-1 09:00-09:15</p>	<p>Controlled Growth Saturation Behavior of Ultrathin Ru Film Using Electric Field/Potential Assisted Atomic Layer Deposition (EA-ALD) Yoon Jeong Kim, Ji Won Han, and Tae Joo Park <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>WA1-D-2 09:15-09:30</p>	<p>Atomic Layer Deposition of Metal Thin Film Using Discrete Feeding Method (DFM) and Electric Field/Potential Assisted-Atomic Layer Deposition (EA-ALD) Ji Won Han, Hyun Soo Jin, Yoon Jung Kim, and Tae Joo Park <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>WA1-D-3 09:30-09:45</p>	<p>ALD TaAlN Metal Gate Using TaCl₅ and TMA Precursors Moonsuk Choi, Juhyeon Lee, Minhyuk Kim, Wei Nan Jin, Seon Woong Jung, and Changhwan Choi <i>Division of Materials Science and Engineering, Hanyang University</i></p>
<p>WA1-D-4 09:45-10:00</p>	<p>Co Liner Impact on Microstructure of Cu(Mn) Alloy Interconnects Byeong Hwa Jeong^{1,3}, Seung Han Lee³, Sang Ho Lee³, and Geun Young Yeom^{1,2} ¹<i>School of Advanced Materials Science and Engineering, Sungkyunkwan University,</i> ²<i>SKKU Advanced Institute of Nano Technology (SAINT), Sungkyunkwan University,</i> ³<i>Korea Institute for Super Materials, ULVAC KOREA, Ltd.</i></p>
<p>WA1-D-5 10:00-10:15</p>	<p>Low-resistivity Molybdenum Nitride Thin Films Deposited by Atomic Layer Deposition Using a New Precursor Min-Ji Ha, Jeong-Hun Choi, and Ji-Hoon Ahn <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>WA1-D-6 10:15-10:30</p>	<p>Enhanced Selectivity of Atomic Layer Deposited Ru Thin Films through the Discrete Feeding of Aminosilane Inhibitor Molecules Jeong-Min Lee, Jinseon Lee, Ji Won Han, Tae Joo Park, and Woo-Hee Kim <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>